

15824 U.S. PTO  
10/07/02

NOV 18 2002

U.S. UTILITY Patent Application



APPL NUM	FILING DATE	CLASS	SUBCLASS	GAU	EXAMINER
10073119	02/12/2002	396	35	2851	H. Nguyen

**APPLICANTS:** Baselmans Johannes; Moers Marco; Van Der Laan Hans; Willekers Robert; De Boei Wilhelmus; Ven De Kerckhof Marcus;

**\*\*CONTINUING DATA VERIFIED:**

**\*\* FOREIGN APPLICATIONS VERIFIED:**  
EUROPEAN PATENT OFFICE (EPO) 01301283.6 02/13/2001

PG-PUB DO NOT PUBLISH <input type="checkbox"/>	RESCIND <input type="checkbox"/>
Foreign priority claimed <input checked="" type="checkbox"/> yes <input type="checkbox"/> no	ATTORNEY DOCKET NO
35 USC 119 conditions met <input checked="" type="checkbox"/> yes <input type="checkbox"/> no	P 290667 P-0234.010
Verified and Acknowledged Examination Article: HW	
TITLE: Lithographic projection apparatus, a grating module, a sensor module, a method of measuring wave front aberrations	

**ISSUE FEE IN FILE**

10.5-15 Formal Drawings (2 shs) set 1 6/12/02

<b>NOTICE OF ALLOWANCE MAILED</b> 6/18/03		<b>CLAIMS ALLOWED</b> Total Claims 15 Print Claim for 0.6/1/	
<b>ISSUE FEE</b> Amount Due 1600 Date Paid 09/16/03		<b>DRAWING</b> Sheets Drawn 7 Figs Drawn 13 Print Figs 2	
<b>TERMINAL DISCLAIMER</b>		<b>PREPARED FOR ISSUE</b> Application Examiner 6/18/03	
<b>WARNING:</b> The information disclosed herein may be restricted. Unauthorized disclosure may be prohibited by the United States Code Title 35 Sections 122, 181 and 368. Possession outside the U.S. Patent & Trademark Office is restricted to authorized employees and contractors only.			

FILED WITH ☒ DISK (CRF) ☒ CD-ROM  
(Attached in pocket on right inside flap)

BEST AVAILABLE COPY